

Notice of References Cited	Application/Control No. 10/719,083	Applicant(s)/Patent Under Reexamination HWANG ET AL.	
	Examiner Patricia A. George	Art Unit 1765	Page 1 of 1

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NON-PATENT DOCUMENTS

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	W	SPI conference proceedings; Proc. SPIE Vol.3999, March 2000; High Performance 193-nm Possitive Resist Using Alternating Polymer Systems of Functionalized Cyclic Olefins/Maleic Anhydride also published at JRS Corporation in 2002
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.